Georgia | Research Tech | Corporation

OFFICE OF TECHNOLOGY LICENSING

https://licensing.research.gatech.edu | techlicensing@gtrc.gatech.edu

Technologies

Available for LICENSING

A Process to Chemically Modify Polymeric Materials

A process that chemically modifies polymeric materials through static, low-pressure infiltration

Inventors at Georgia Tech have advanced a process called Vapor Phase Infiltration (VPI) that requires only a single exposure cycle to convert microns of polymer into a hybrid material. VPI can chemically modify a variety of polymeric materials in a variety of form factors using low-pressure, highly reactive gases. This technology utilizes the following steps: sorption, diffusion, and entrapment. During sorption, a gaseous metalorganic precursor is dissolved into a polymer. The precursor then migrates during the diffusion step. In entrapment, the precursor is immobilized through reaction or steric hindrance.

Summary Bullets

- Cost reduction cost is reduced due to technique simplification
- Efficiency technique has no requirement for repeated cycling
- Flexibility VPI can be applied at any stage in production processes

Solution Advantages

- Cost reduction cost is reduced due to technique simplification
- Efficiency technique has no requirement for repeated cycling
- Flexibility VPI can be applied at any stage in production processes
- **Increased reliability** chemical properties are more stabilized

Potential Commercial Applications

Manufacturing for:

- Polymer Membranes
- Polymer Fabrics / Textiles
- Polymer Films
- Polymer Foams
- Bulk Polymers
- Polymer Powders / Microspheres

Background and More Information

Atomic Layer Deposition (ALD) is a surface-controlled process that results in the deposition of thin films one layer at a time. Each atomic layer that is formed by this sequential process is a result of saturated surface-controlled reactions. In ALD, increasing processing volume presents significant challenges to the fluid dynamics in the chamber, with unpredictable effects on the quality of the film deposition. Additionally, long cycle times and the layer-by-layer nature of ALD result in slow deposition rates. There is a need to develop a more efficient process to modify polymeric materials.

Inventors

- Dr. Mark Losego Assistant Professor - Georgia Tech School of Materials Science and Engineering
- Brandon Piercy
 Georgia Tech School of Materials Science and Engineering
- Collen Z. Leng Leng Graduate Student – Georgia Tech School of Materials Science and Engineering

IP Status

: US10364491B2

Publications

Images

, -

After Exposure to 60°C Toluene for 30 min



Visit the Technology here: A Process to Chemically Modify Polymeric Materials

As Synthesized

https://s3.sandbox.research.gatech.edu//index.php/print/pdf/node/3440